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In re Issued Patent:

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For: HIGH DENSITY PLASMA CHEMICAL  
VAPOR DEPOSITION PROCESS

Group Art Unit: 1112

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INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. § 1.97(i), please place the attached Form 1449 and the enclosed copy of the listed patents in the above-referenced file. In submitting these references, no representation is made or implied that the references are or are not material.

This Information Disclosure Statement is filed with no request for consideration of this reference. Accordingly, no fee is believed due. However, any fee associated herewith may be charged to Deposit Account No. 50-1223.

Respectfully submitted,

10/27/04  
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